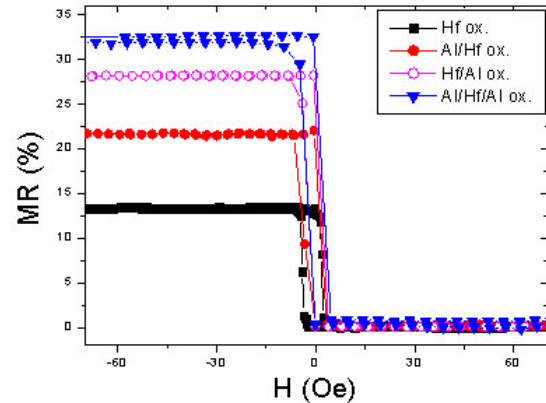


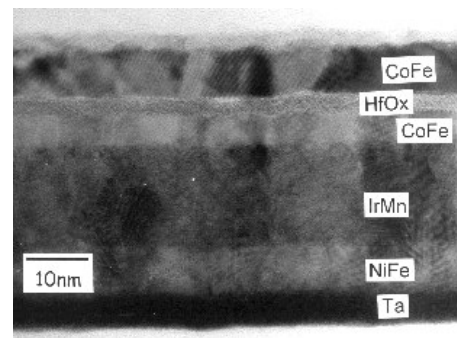
ATS-PVD Series UHV Sputter System with 8x3" Guns



Magnetic resistance of ferromagnetic multilayer



TEM analysis of ferromagnetic multilayer

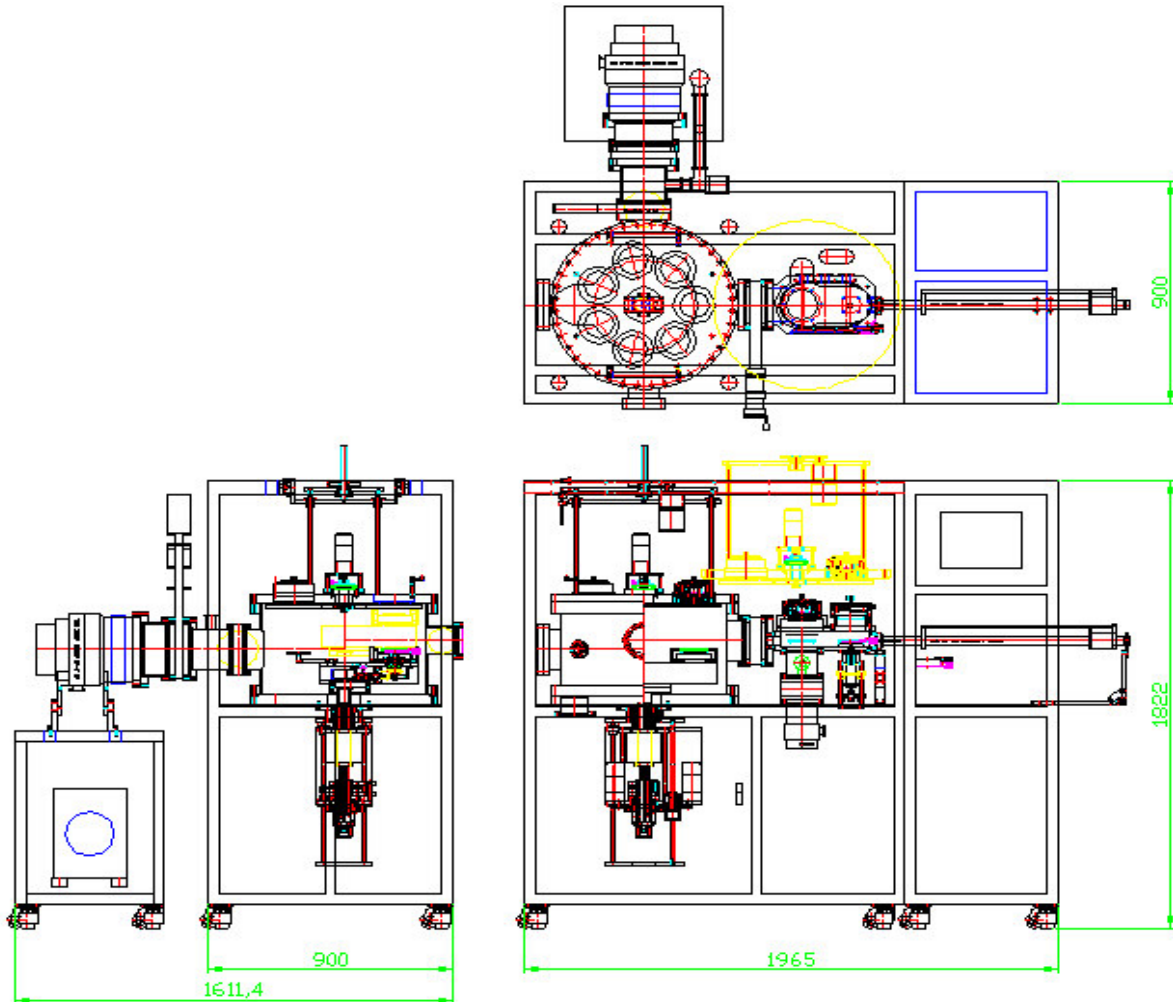


Special Features

- ◆ Ultrahigh vacuum sputter system for R&D and small scale production (base pressure: up to $\sim 10^{-9}$ Torr obtained with only mechanical & turbo molecular pumps)
- ◆ Ferromagnetic metals preheated and predeposited in load-lock chamber
- ◆ Substrate rotation system to be automatically positioned
- ◆ Applications
Ferromagnetic materials deposition for MRAM and hard disk products

- ◆ Wafer capacity
 $7 \times 3''$
- ◆ Average throughput
Up to 30,000 wafers per year
- ◆ Dimension
 $1,965L \times 1,720H \times 1,400W$ (mm)
- ◆ Others
Power : DC 500W 2ea, DC 1500W 1ea
Gas : Ar
Pump : rotary(970l/min for process chamber & 600l/min for loadlock chamber) & turbo(1,380l/s)
Heater : halogen lamp in loadlock chamber (max. 700°C)

◇ Layout



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